

L Number	Hits	Search Text	DB	Time stamp
-	14260	CMP or "chemical mechanical polishing"	USPAT; US-PGPUB	2002/02/08 11:31
-	725	("438/624").CCLS.	USPAT; US-PGPUB	2002/02/08 09:58
-	322	(CMP or "chemical mechanical polishing") and (("438/624").CCLS.)	USPAT; US-PGPUB	2002/02/08 09:59
-	4981	ILD or interlevel	USPAT; US-PGPUB	2002/02/08 11:31
-	80162	nitride or oxynitride	USPAT; US-PGPUB	2002/02/08 10:00
-	92	((CMP or "chemical mechanical polishing") and (("438/624").CCLS.)) and (ILD or interlevel)	USPAT; US-PGPUB	2002/02/08 10:00
-	77	(nitride or oxynitride) and (((CMP or "chemical mechanical polishing") and (("438/624").CCLS.)) and (ILD or interlevel))	USPAT; US-PGPUB	2002/02/08 11:57
-	393	438/633.ccls.	USPAT; US-PGPUB	2002/02/08 10:44
-	1190	(CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)	USPAT; US-PGPUB	2002/02/08 10:45
-	79	438/633.ccls. and ((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride))	USPAT; US-PGPUB	2002/02/08 10:59
-	1730	438/257-267.ccls.	USPAT; US-PGPUB	2002/02/08 11:00
-	30	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/257-267.ccls.	USPAT; US-PGPUB	2002/02/08 11:04
-	934	438/692.ccls.	USPAT; US-PGPUB	2002/02/08 11:04
-	128	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/692.ccls.	USPAT; US-PGPUB	2002/02/08 11:21
-	564	438/763.ccls.	USPAT; US-PGPUB	2002/02/08 11:22
-	14	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/763.ccls.	USPAT; US-PGPUB	2002/02/08 11:25
-	189	438/791.ccls.	USPAT; US-PGPUB	2002/02/08 11:25
-	7	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/791.ccls.	USPAT; US-PGPUB	2002/02/08 11:26
-	125	438/786.ccls.	USPAT; US-PGPUB	2002/02/08 11:26
-	6	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/786.ccls.	USPAT; US-PGPUB	2002/02/08 11:29
-	80	438/902.ccls.	USPAT; US-PGPUB	2002/02/08 11:29
-	2	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/902.ccls.	USPAT; US-PGPUB	2002/02/08 11:30
-	6392	CMP or "chemical mechanical polishing"	EPO; JPO; DERWENT	2002/02/08 11:31
-	1136	ILD or interlevel	EPO; JPO; DERWENT	2002/02/08 11:31
-	437	438/for.388.ccls.	EPO; JPO; DERWENT	2002/02/08 11:32
-	0	438/for.388.ccls. and ((CMP or "chemical mechanical polishing") and (ILD or interlevel))	EPO; JPO; DERWENT	2002/02/08 11:32
-	862	438/for.395.ccls.	EPO; JPO; DERWENT	2002/02/08 11:32
-	0	((CMP or "chemical mechanical polishing") and (ILD or interlevel)) and 438/for.395.ccls.	EPO; JPO; DERWENT	2002/02/08 11:32
-	50	(CMP or "chemical mechanical polishing") and (ILD or interlevel)	EPO; JPO; DERWENT	2002/02/08 11:33
-	21418	lapp\$	USPAT; US-PGPUB	2002/02/08 12:02
-	12	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and lapp\$	USPAT; US-PGPUB	2002/02/08 12:40

-	9	lap with CMP	USPAT; US-PGPUB	2002/02/08 12:41
-	23	lap\$ with CMP	USPAT; US-PGPUB	2002/02/08 12:41
-	14	(lap\$ with CMP) not (lap with CMP)	USPAT; US-PGPUB	2002/02/08 12:47
-	94	abrad\$ with CMP	USPAT; US-PGPUB	2002/02/08 12:48
-	92	(abrad\$ with CMP) not (lap\$ with CMP)	USPAT; US-PGPUB	2002/02/08 12:48
-	21	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and ((abrad\$ with CMP) not (lap\$ with CMP))	USPAT; US-PGPUB	2002/02/08 12:49
-	1	((((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and ((abrad\$ with CMP) not (lap\$ with CMP))) and BPSG	USPAT; US-PGPUB	2002/02/08 13:41
-	632	438/622.ccls.	USPAT; US-PGPUB	2002/02/08 13:41
-	62	((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/622.ccls.	USPAT; US-PGPUB	2002/02/08 13:42
-	2441661	Al or aluminum	USPAT; US-PGPUB	2002/02/08 13:45
-	62	((((CMP or "chemical mechanical polishing") and (ILD or interlevel) and (nitride or oxynitride)) and 438/622.ccls.) and (Al or aluminum)	USPAT; US-PGPUB	2002/02/08 13:50